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PATENT

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Applicant : Nicholas F. Borrelli, Thomas P. Seward III,
and Charlene M. Smith
Serial No. : Not Yet Assigned
Filed : Simultaneously Herewith
For : SILICA WITH LOW COMPACTION UNDER HIGH
ENERGY IRRADIATION

Commissioner of Patents and Trademarks
Washington, D.C. 20231

MODIFIED 1449 FORM

<u>Examiner Initial</u>		<u>Document Number</u>	<u>Issue Date</u>	<u>Name</u>
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